

FORMING A TRANSPARENT WINDOW IN A POLISHING PAD
FOR A CHEMICAL MECHANICAL POLISHING APPARATUS

ABSTRACT OF THE DISCLOSURE

The polishing pad for a chemical mechanical polishing apparatus, and a method of making the same. The polishing pad has a covering layer with a polishing surface and a backing layer which is adjacent to the platen. A first opening in the covering layer with a first cross-sectional area and a second opening in the backing layer with a second, different cross-sectional area form an aperture through the polishing pad. A substantially transparent polyurethane plug is positioned in the aperture, and an adhesive material fixes the plug in the aperture.

THIS SHEET HAS BEEN
REPLACED

This Sheet Has Been Replaced

